

<b>Notice of References Cited</b>	Application/Control No. 09/812,365	Applicant(s)/Patent Under Reexamination KUSUNOKI ET AL.	
	Examiner Russell Frejd	Art Unit 2128	Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-			
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**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
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